

1763

PATENT
Attorney Docket No. 7363.0010

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Reissue Application of:

U.S. Patent No.: 5,792,261

Inventor: Kiichi HAMA et al.

Issued: August 11, 1998

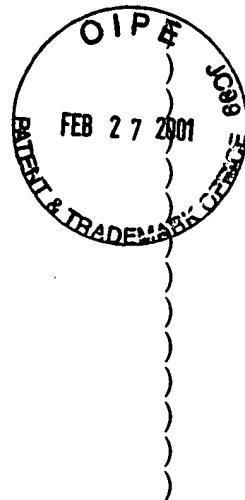
Serial No.: 09/478,370

Filed: January 6, 2000

For: PLASMA PROCESS
APPARATUS

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:



Group Art Unit: 1763

Examiner: Alejandro Mulero, L.

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AMENDMENT

In response to the Office Action dated December 27, 2000, please amend this reissue application as follows:

IN THE CLAIMS:

1. (Amended) An apparatus for processing a process region of a substrate:
using a plasma, comprising:
 - a container substantially formed of a conductive material;
 - a partition plate dividing said container into an air-tight process chamber and an air-tight auxiliary chamber, and having a window plate made of dielectric;
 - a main exhaust pump [exhaust] for exhausting and setting said process chamber to a vacuum;